

# Silicon n-in-p Pixel Sensors for future ATLAS Upgrades

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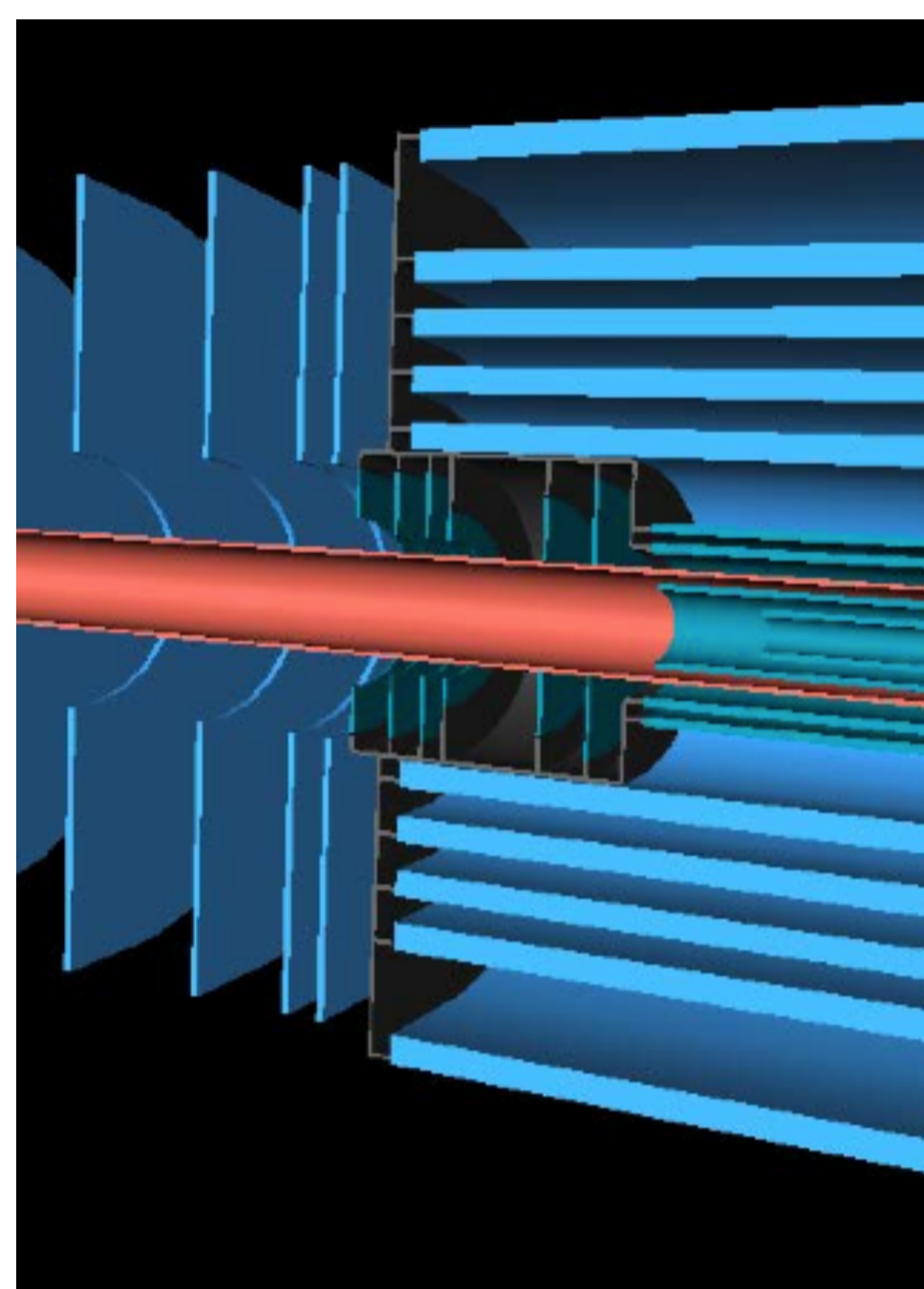
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## Introduction

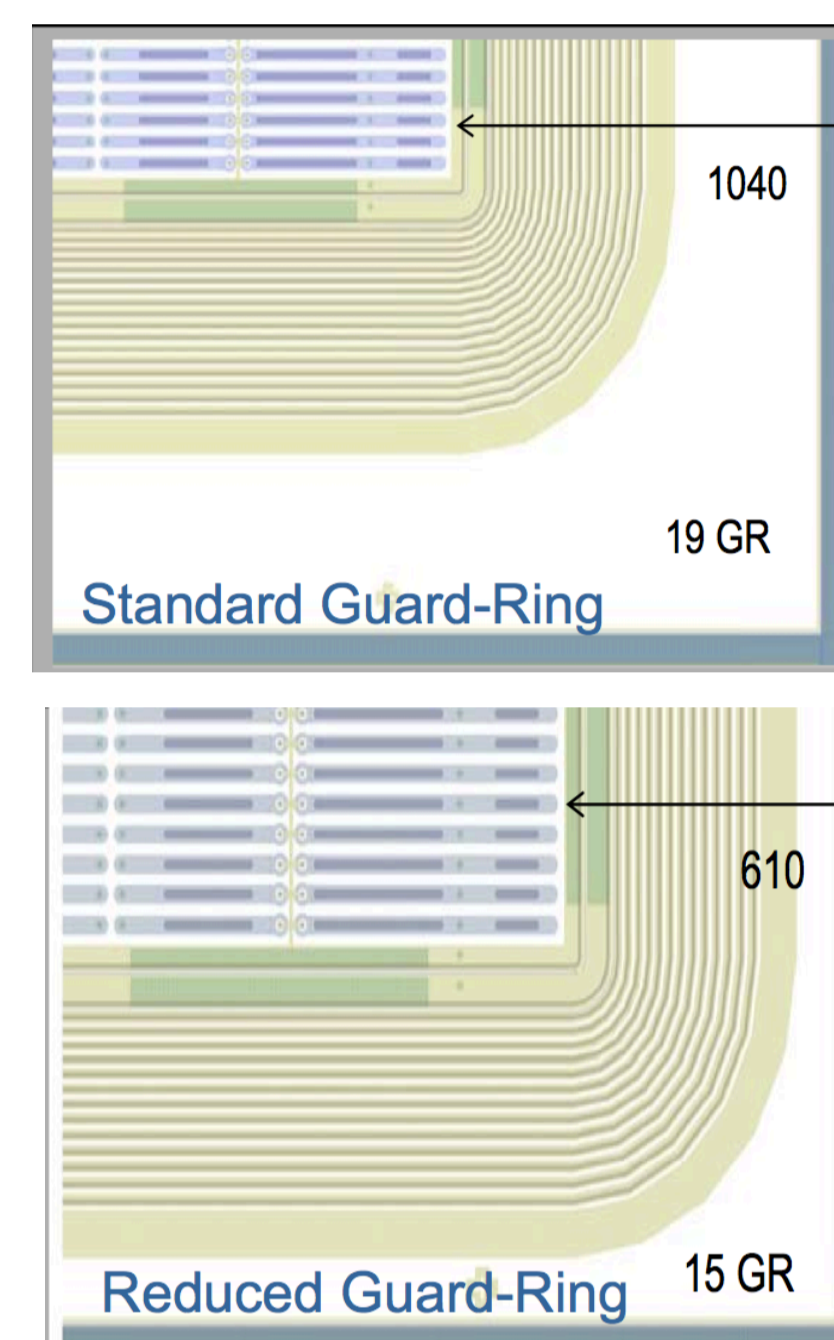
ATLAS Pixel Detector Upgrade:



- **2022 (Phase 2):** Inner detector Tracker (ITK)
  - Complete new ATLAS tracker (Pixel and Strip detectors)
  - Much larger Pixel surface w.r.t. current Pixel Detector:  $\sim 7\text{-}10\text{ m}^2$
  - Luminosity:  $5 \times 10^{34}\text{ cm}^{-2}\text{s}^{-1}$
  - Radiation dose (innermost layer):  $2 \times 10^{16}\text{ 1-MeV } n_{\text{eq}}\text{ cm}^{-2}$
- **Planar n-in-p as future sensor technology:**
  - Excellent candidate for large volume
  - Single side processing  $\rightarrow$  reduced cost
  - Radiation hardness comparable to n-in-n

## Sensor description

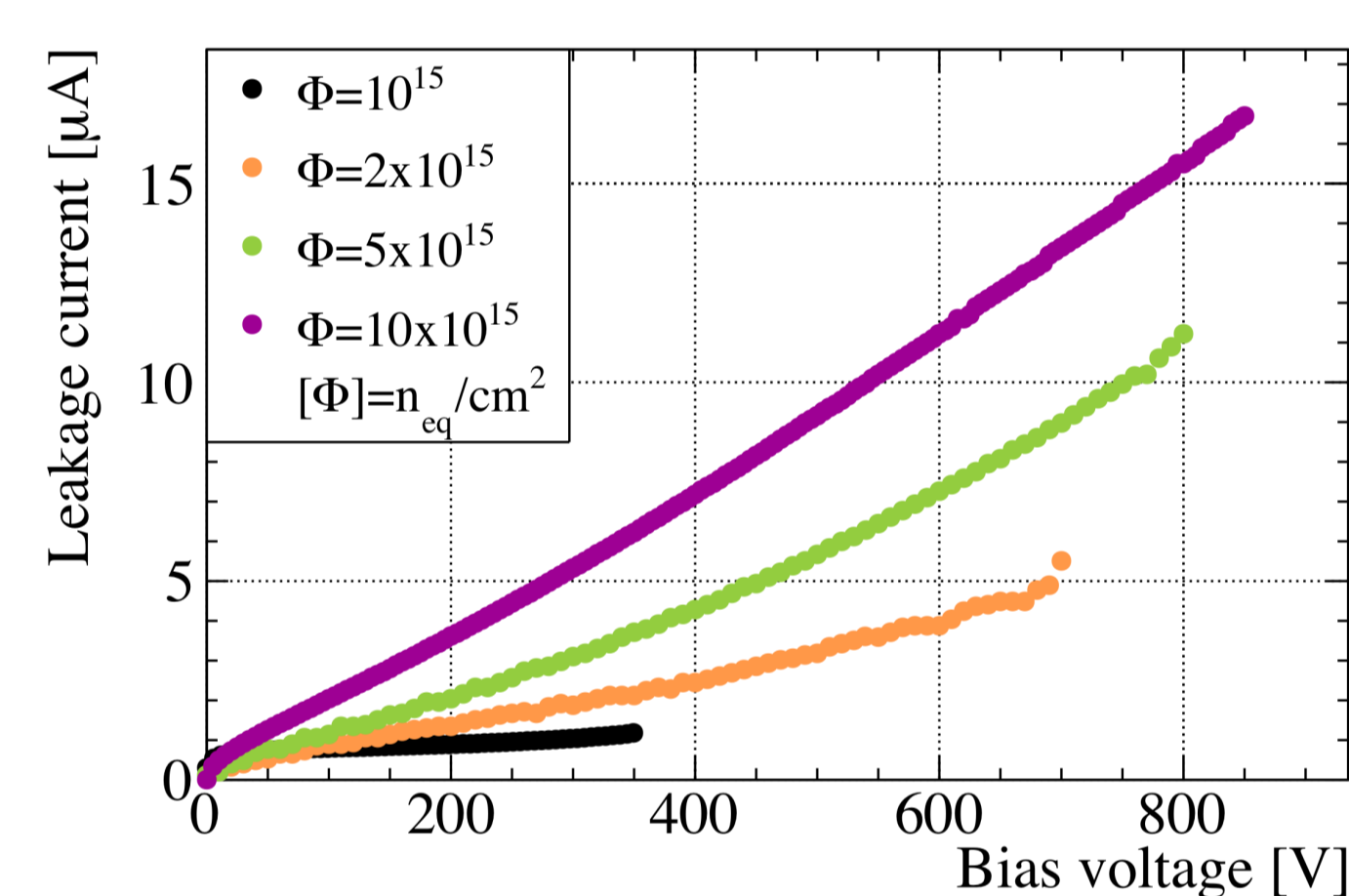
First CiS n-in-p Pixel production



- Production on 4" Fz p-type wafer, 285  $\mu\text{m}$  thick
- Inter-pixel isolation:
  - Moderated p-spray
  - Homogeneous p-spray
- Bump bonding to the ATLAS Pixel Front-End Chip (FE-I3) performed by IZM-Berlin
- BCB layer deposited on the sensor front side as an isolation to prevent sparks between sensor and chip

## Test Results

### Leakage currents (after irradiation)



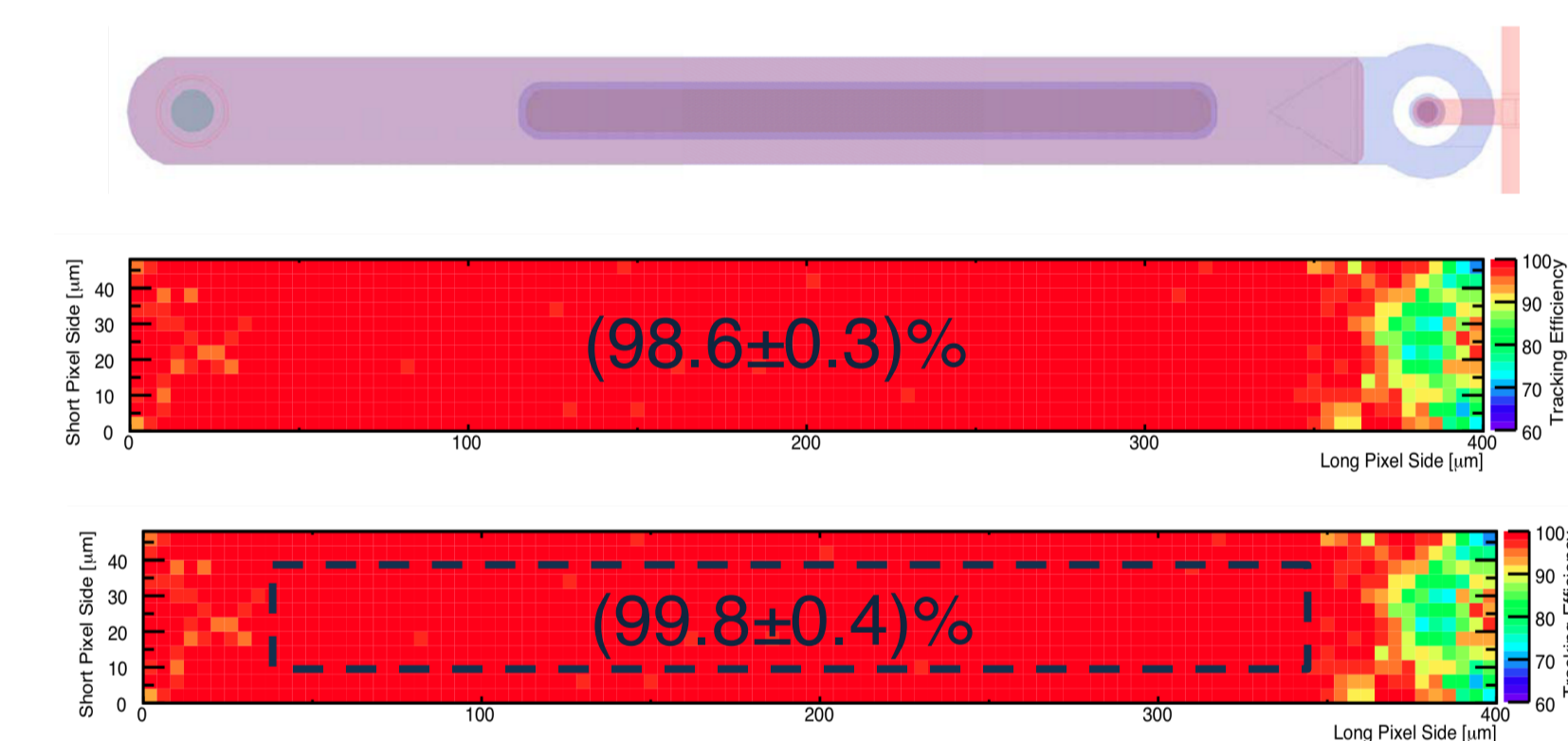
**Before irradiation (at +20°C)**  
All modules show leakage currents below 6  $\mu\text{A}$ , with a bias voltage of 150 V [1,2,3].

**After irradiation (scaled at -20°C)**  
The breakdown voltages shifted to higher values and for the highest fluence it exceeds 800 V. Also the leakage currents show higher values with increasing fluences.

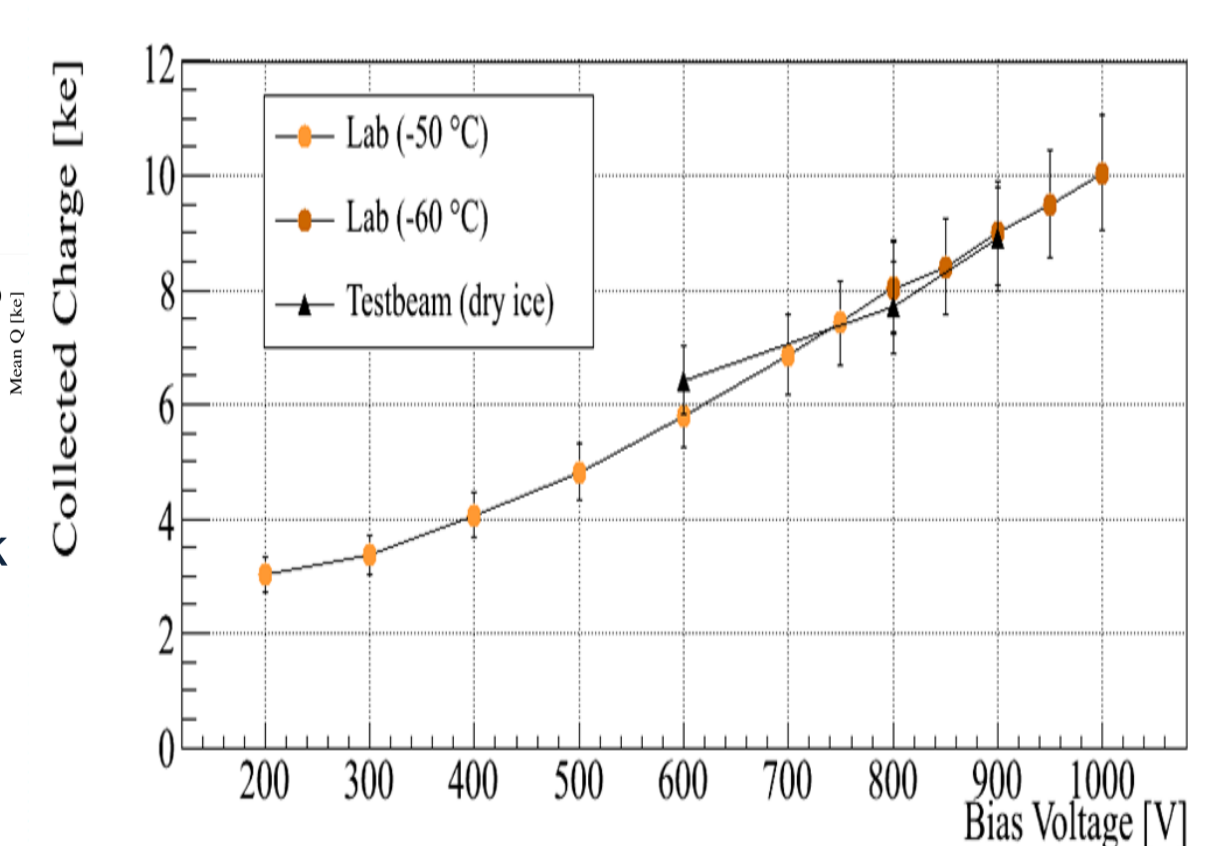
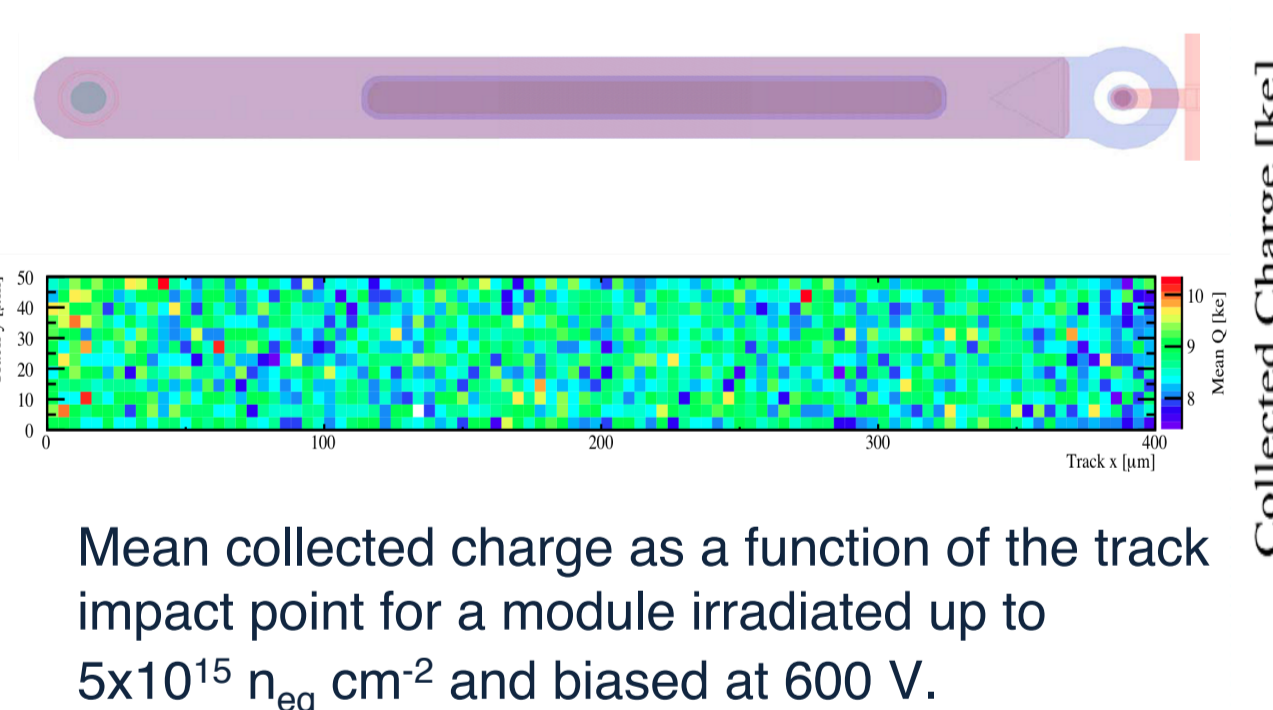
### Beam test at the CERN SPS with a 120 GeV/c $\pi^+$ beam

#### Tracking efficiency

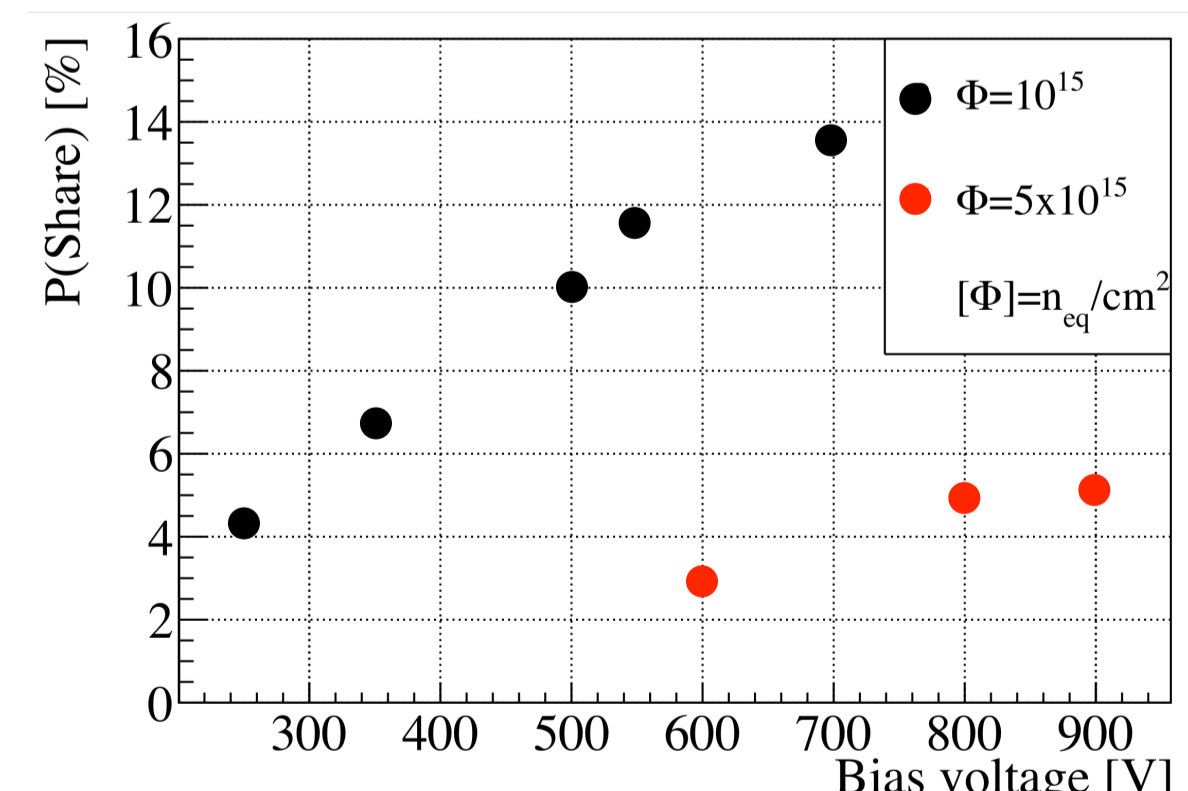
Mean tracking efficiency as a function of the track impact point for a module irradiated up to  $5 \times 10^{15}\text{ n}_{\text{eq}}\text{ cm}^{-2}$  and biased at 600V [2,4].



#### Charge collection



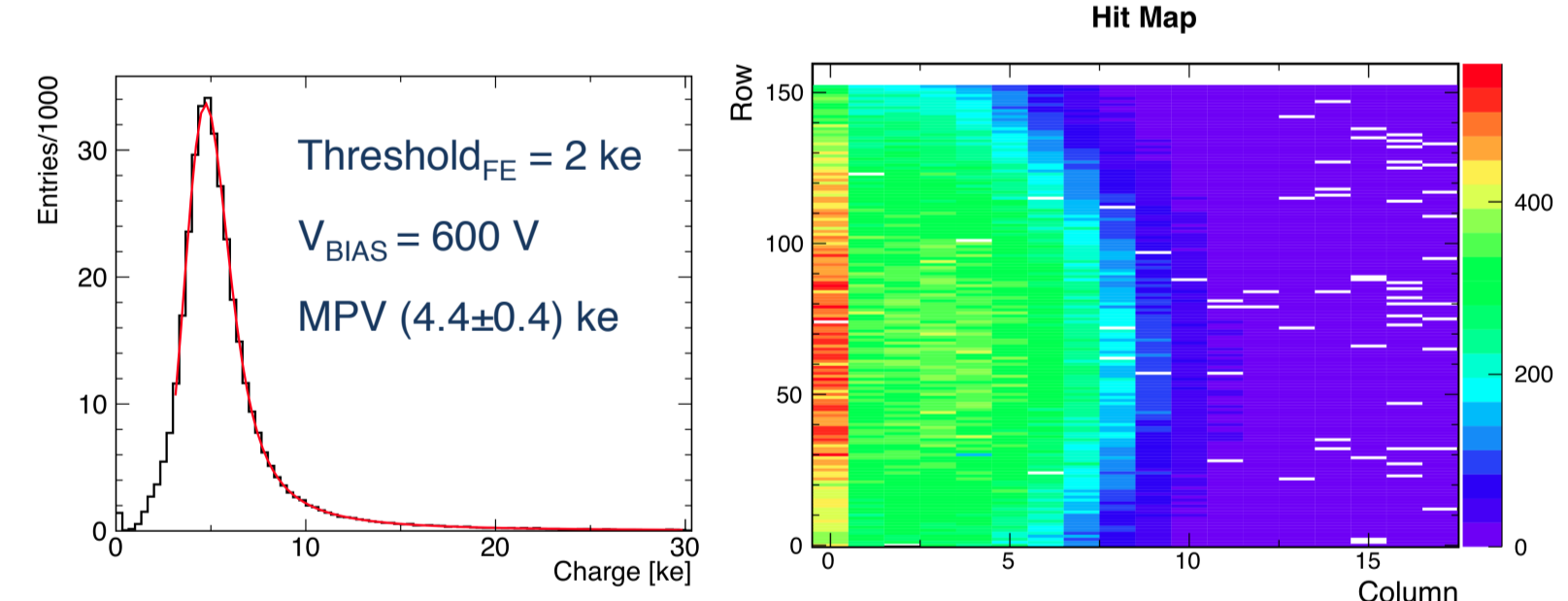
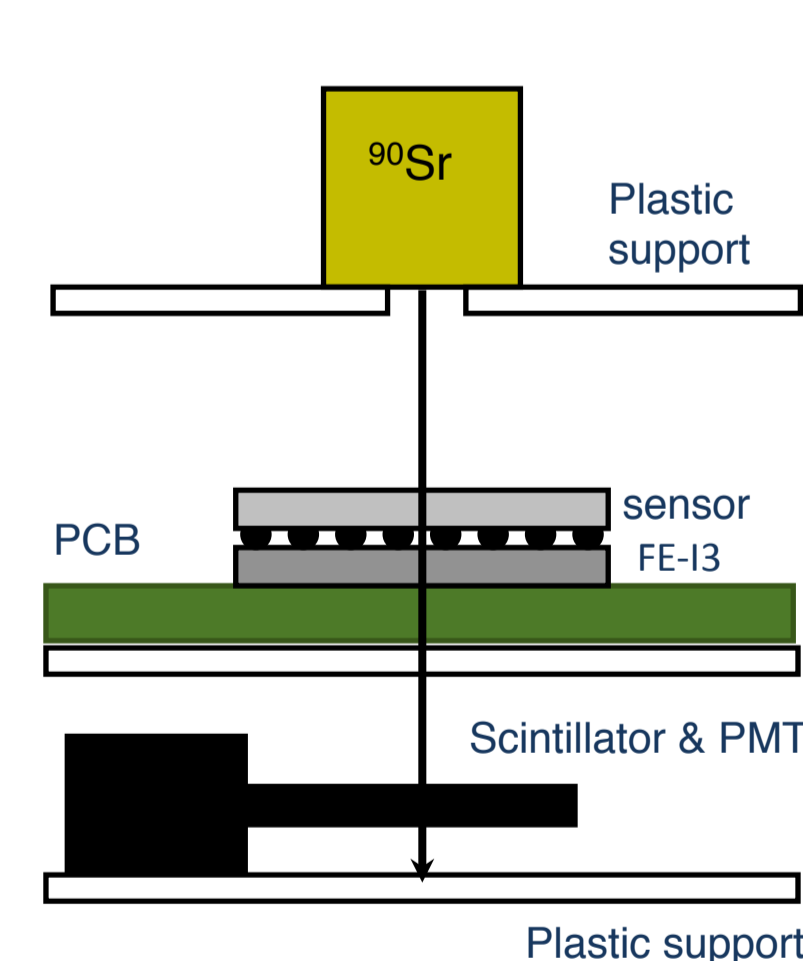
#### Charge sharing



Dependence of charge sharing P(Share) probability as a function of the bias voltage for modules irradiated up to  $10^{15}\text{ n}_{\text{eq}}\text{ cm}^{-2}$  and  $5 \times 10^{15}\text{ n}_{\text{eq}}\text{ cm}^{-2}$

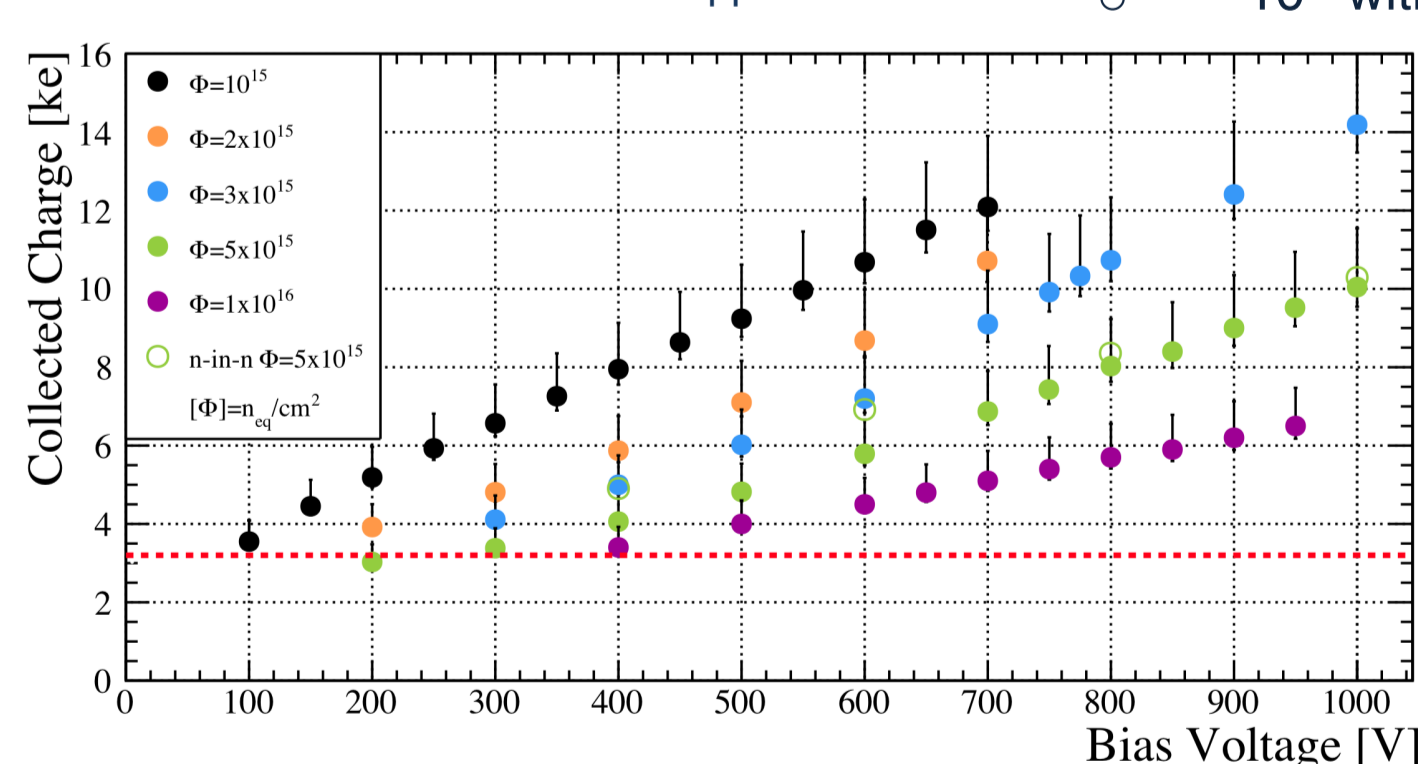
### External-trigger operation with $^{90}\text{Sr}$ source

Collected charge measured with module irradiated up to  $1 \times 10^{16}\text{ n}_{\text{eq}}\text{ cm}^{-2}$



Module irradiated up to  $1 \times 10^{16}\text{ n}_{\text{eq}}\text{ cm}^{-2}$  and biased at 600V:

- Collected charge / Front-end Threshold > 2
- Noise occupancy
  - $10^{-7}$  with 1% masked channels
  - $10^{-6}$  with 0.5% masked channels



Collected charge as a function of the bias voltage with the front-end chip tuned to a threshold of 3.2ke by irradiated modules

Result from n-in-n module are from S. Altenheiner et al., NIM A678 (2011) 25

## Summary and future plans

- Excellent performance of CiS n-in-p modules irradiated up to  $10^{16}\text{ 1-MeV } n_{\text{eq}}\text{ cm}^{-2}$ .
- New production on 4" FZ p-type wafer of 200 $\mu\text{m}$  and 300 $\mu\text{m}$  thickness compatible with ATLAS IBL front-end chip (FE-I4) processed. Source, beam tests and irradiation up to HL-LHC fluences planned.
- First production of 6" wafers on high resistivity Fz p-type material, with 4-chip and 1-chip modules is foreseen.

## References

- [1] P. Weigell et al., NIM A658 (2011) 36
- [2] C. Gallrapp et al., NIM A679 (2012) 29
- [3] A. Macchiolo et al., arXiv:1110.4468
- [4] J. Weingarten et al., arXiv:1204.1266